

# **MEMS**

## ***its methods and applications***

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CHE 384T – Graduate Student Presentation

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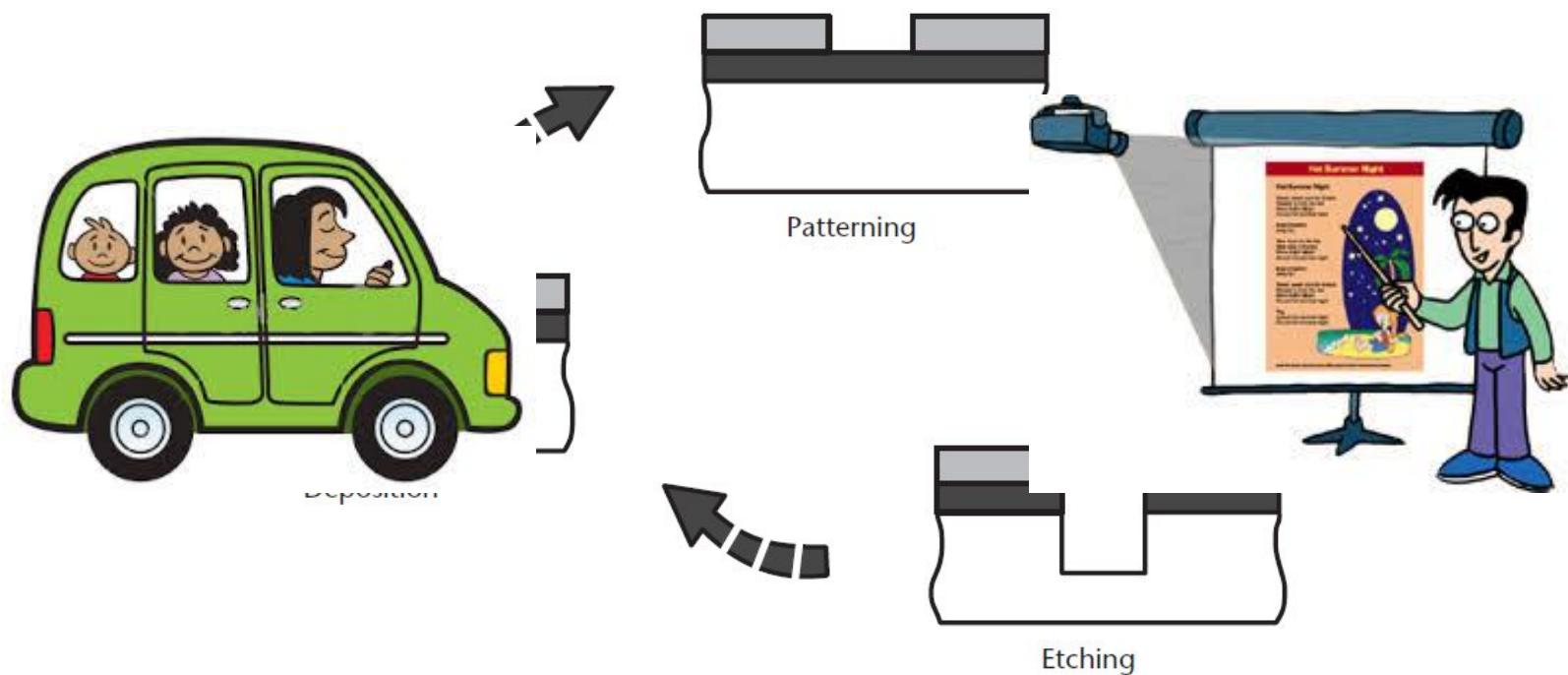
# Contents

- MEMS
- Brief history
- Methods
  - Surface
  - Bulk
  - LIGA
- Applications
  - Industrial & automotive
  - Optical displays
- Outlook



# MEMS - MicroElectroMechanical Systems

- A portfolio of various micromachining techniques & processes to create miniature systems at microscale
- MEMS devices are everywhere





# Early days of MEMS

- Discovery of the piezoresistive effect in silicon by C.S Smith (1954)
  - A change in the electrical resistivity when mechanical strain is applied
- “Silicon as a mechanical material” by Kurt Peterson at IBM (1980s)
  - Pressure sensors, accelerometers, nozzles





# Various methods of MEMS

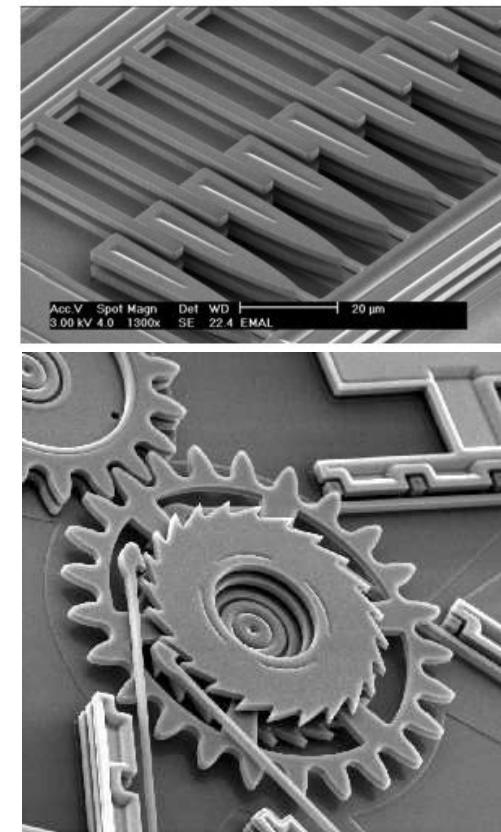
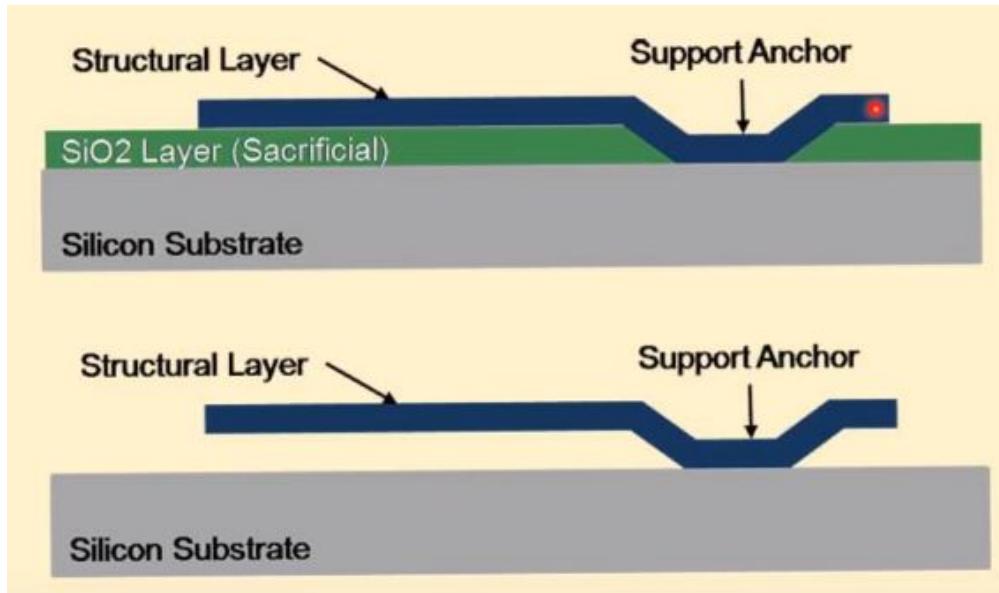
- Surface micromachining
- Bulk micromachining
- **LIGA**





# 1 / Surface micromachining

- Structural and sacrificial layers
- Low aspect ratio

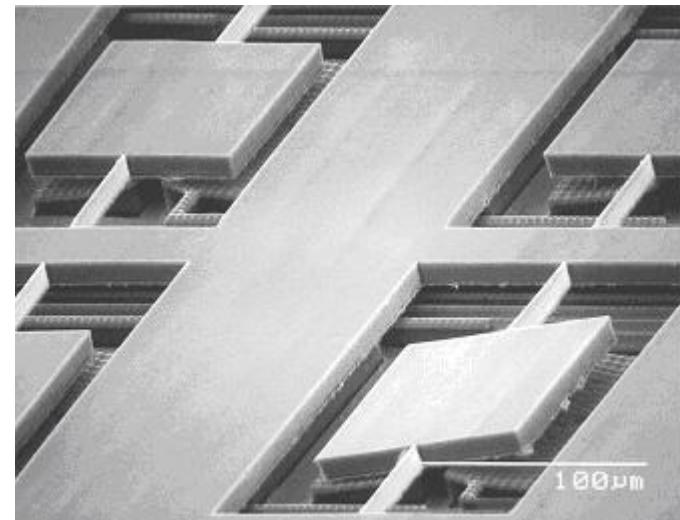
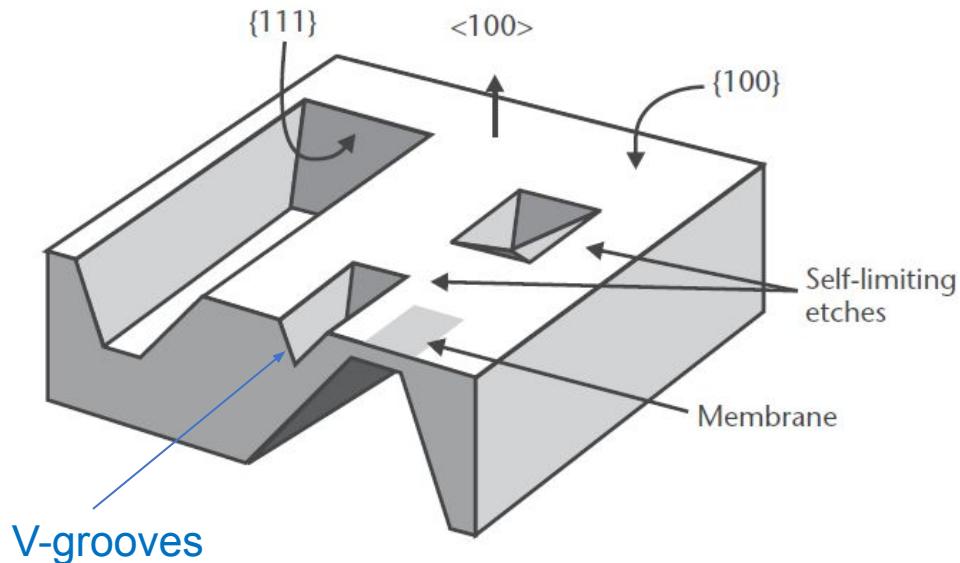




## 2 / Bulk micromachining

- Subtractive process
- Selective (or anisotropic) etching
  - Wet chemical etching
  - Dry plasma etching
- Higher aspect ratio

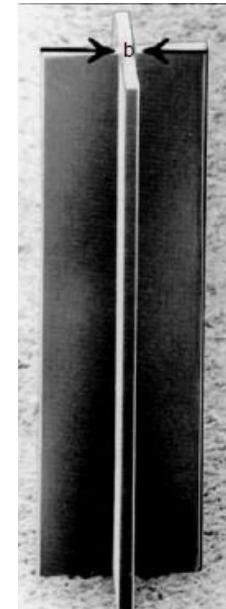
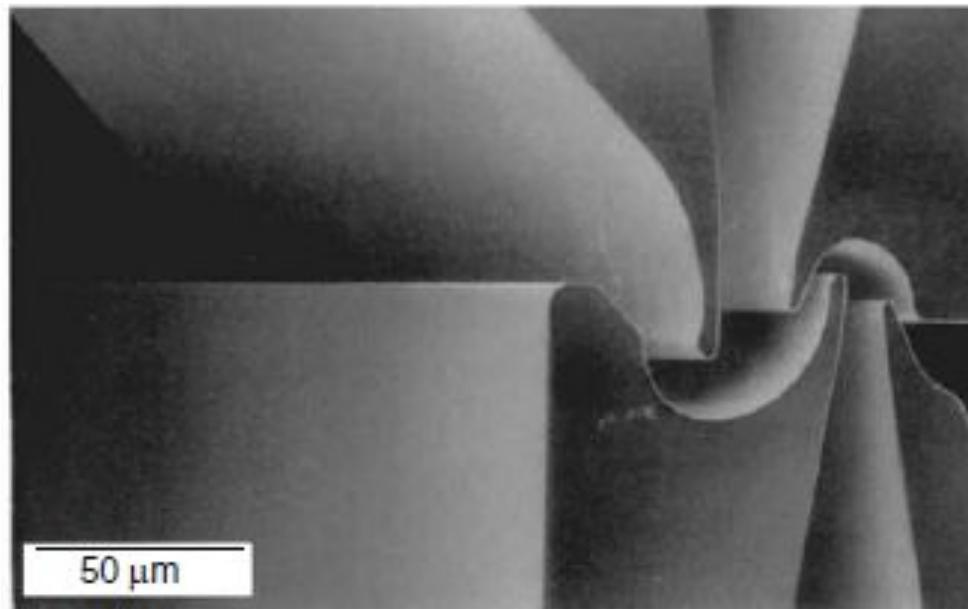
Eg) KOH etch rate:  $\{110\} > \{100\} > \{111\}$





## 3 / LIGA – Lithographie, Galvanoformung, Abformung

- Originally studied for the mass production of micron-sized nozzles for uranium isotopes
- Additive process
- Very high aspect ratio ( $\sim 100$ )
- Vertical & smooth sidewalls

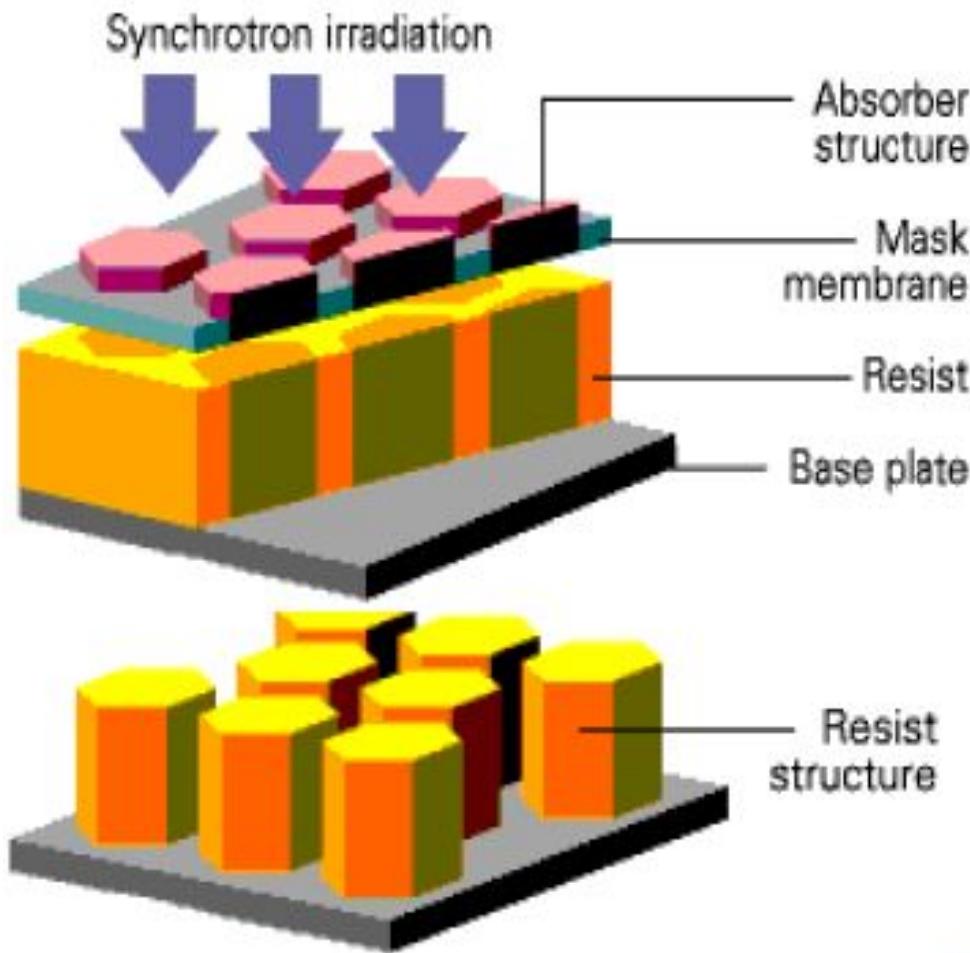


Early 1980s – Karlsruhe nuclear research center in Germany



## 3 / LIGA – Lithography Step

- X-ray proximity printing

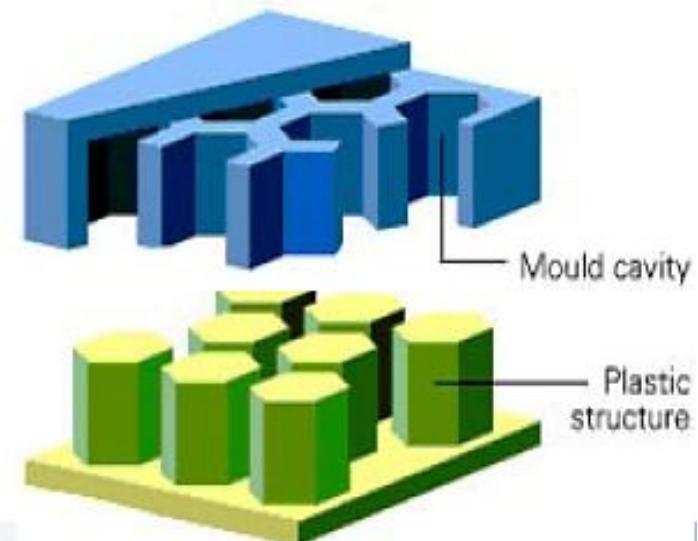
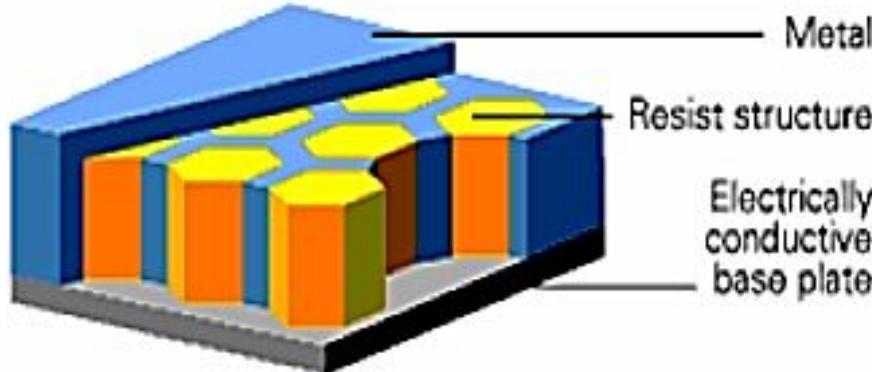


- **X-ray mask**
  - Thick absorber patterns and thin membrane layer
- **Resist**
  - PMMA
- **Base plate**
  - Conducting seed layer (gold/nickel)



## 3 / LIGA – Electroplating & Molding Step

- Immersing in electrolyte baths (e.g. Ni-sulfamate bath)
- Hot embossing/Injection molding
- Demolding with the help of mold release agents (e.g. 3-6 wt% PAT 665) & design shapes





# 3 / LIGA – Making a mold insert for plastic molding

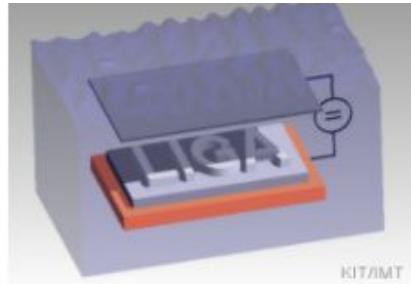


Fig. 29: Nickel electroplating in process

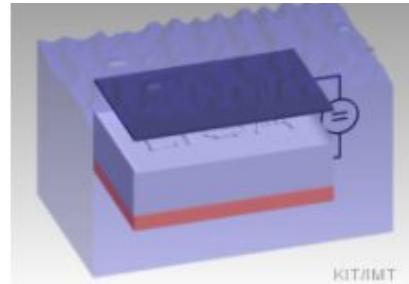


Fig. 30: Nickel electroplating finished

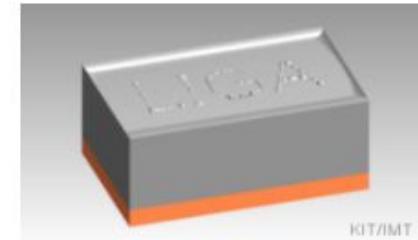


Fig. 31: Nickel mould after electroplating

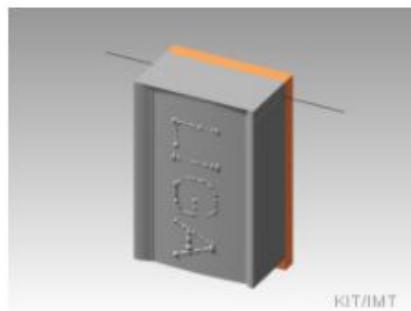


Fig. 32: Wire eroding of the mould, step 1

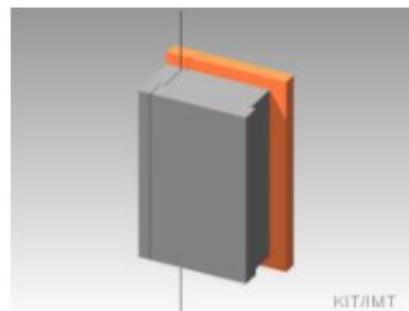


Fig. 33: Wire eroding of the mould, step 2

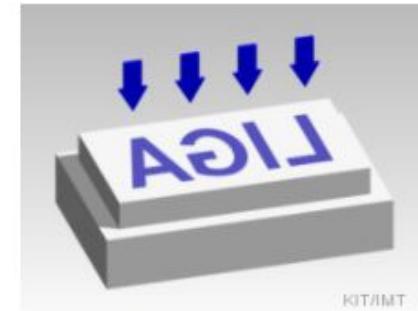


Fig. 34: Flood exposure before resist removing



Fig. 35: Finished nickel mould



Fig. 36: Moulding for mass replication

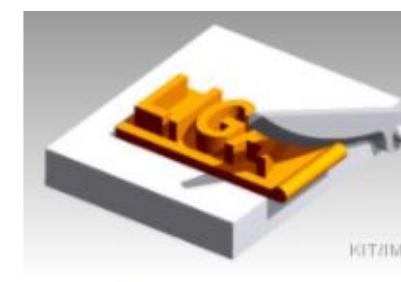
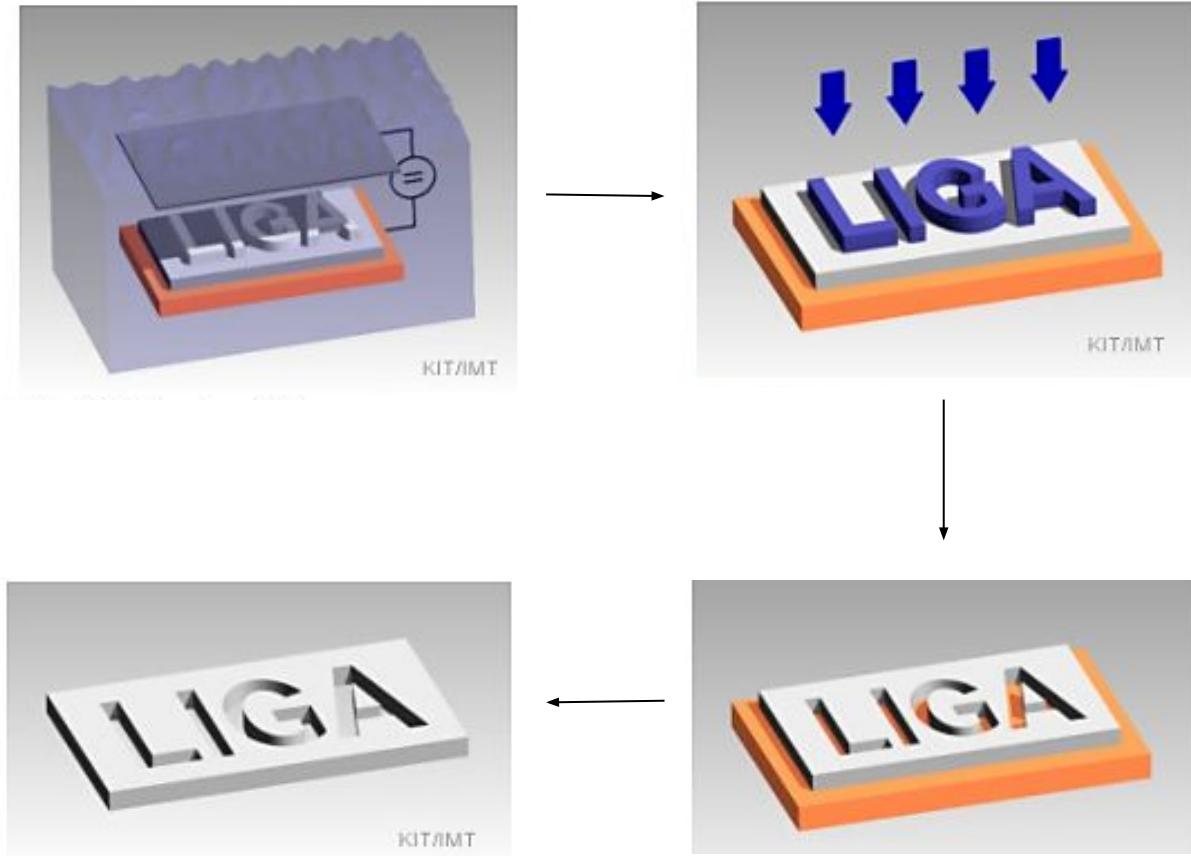


Fig. 37: Final machine finishing



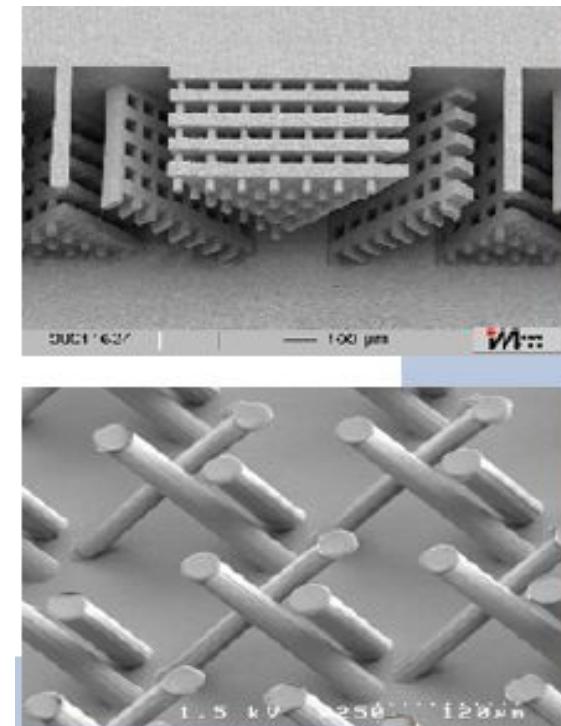
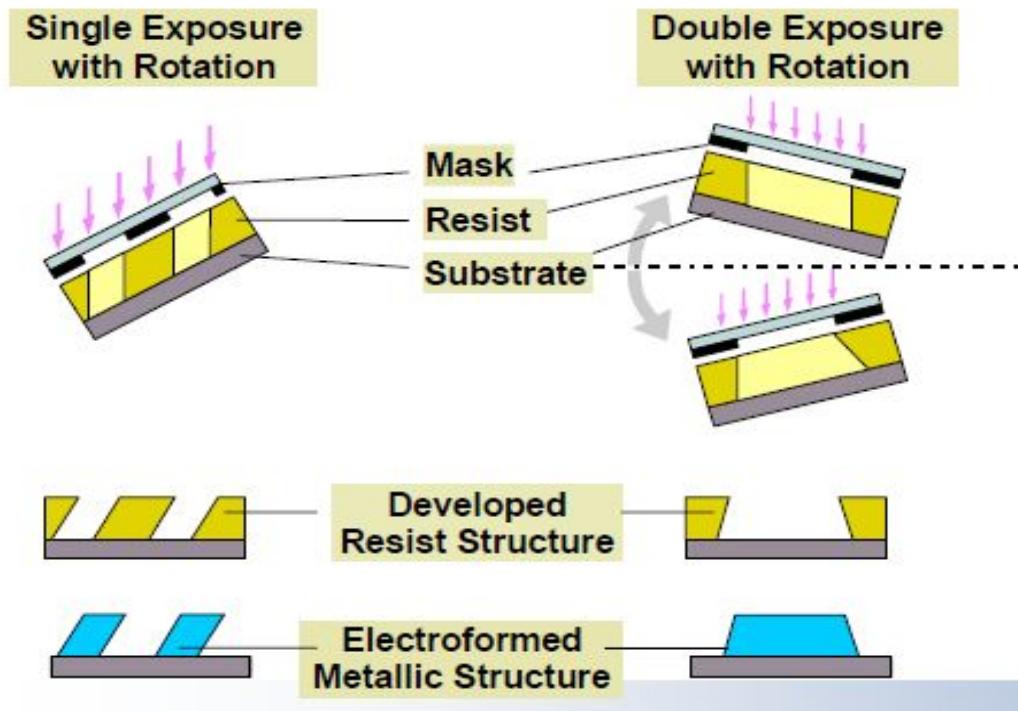
# 3 / LIGA – Making a microstructure





## 3 / LIGA – Slanted Microstructures

- Complex structures can be fabricated by multiple oblique irradiation





# Various applications of MEMS

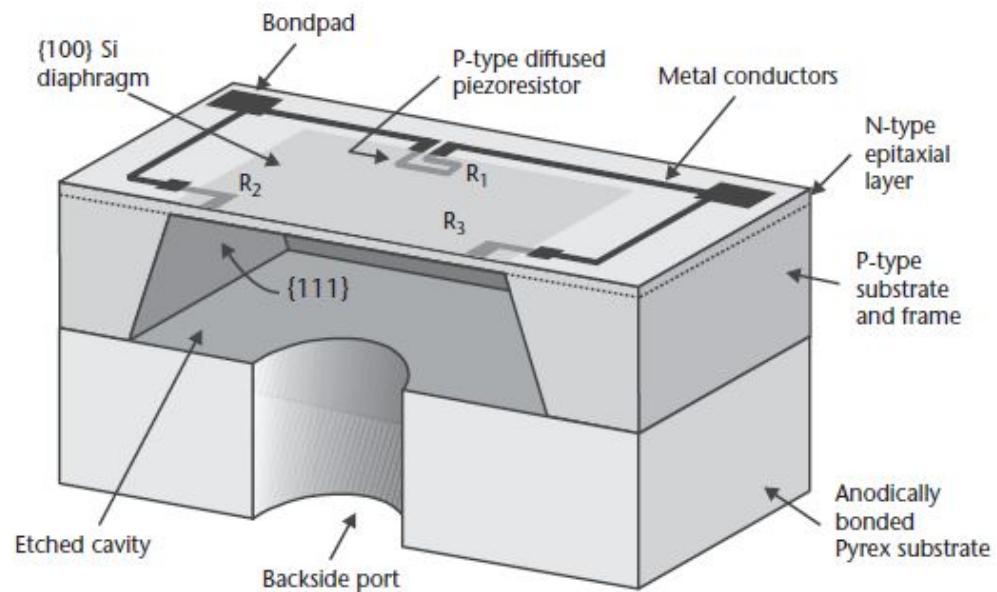
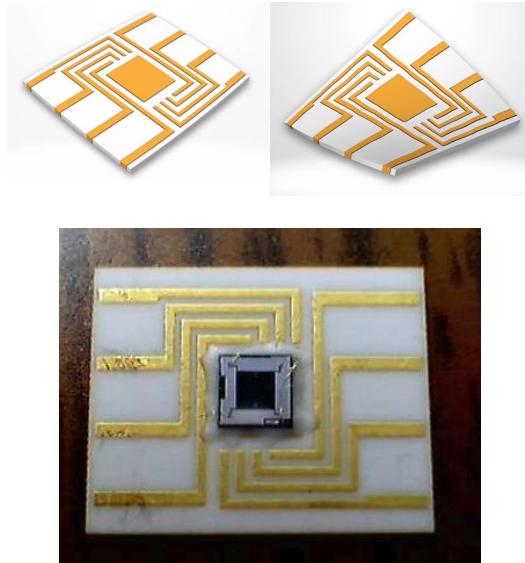
- Industrial & automotive
  - Pressure sensors
  - Accelerometers
  - Nozzles
  - Safety devices for nuclear weapons
- Optical displays
  - Digital micromirrors



# 1 / Industrial & automotive

## • Piezoresistive pressure sensors

- Thin silicon diaphragm
- Mechanical stress causes changes in crystal lattice structure □ electrical resistance changes

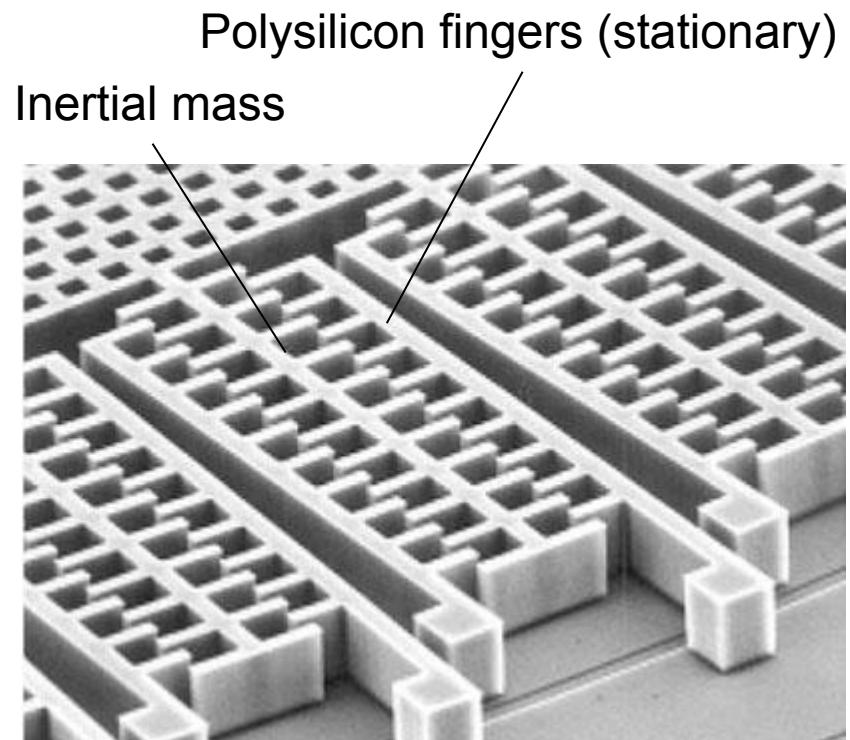
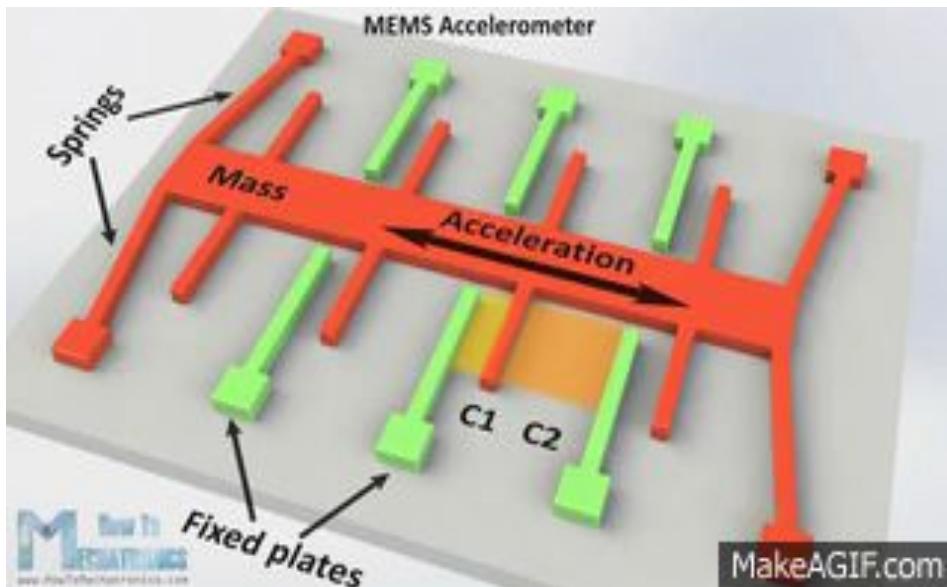




# 1 / Industrial & automotive

## • Accelerometers

- Displacement of the inertial mass

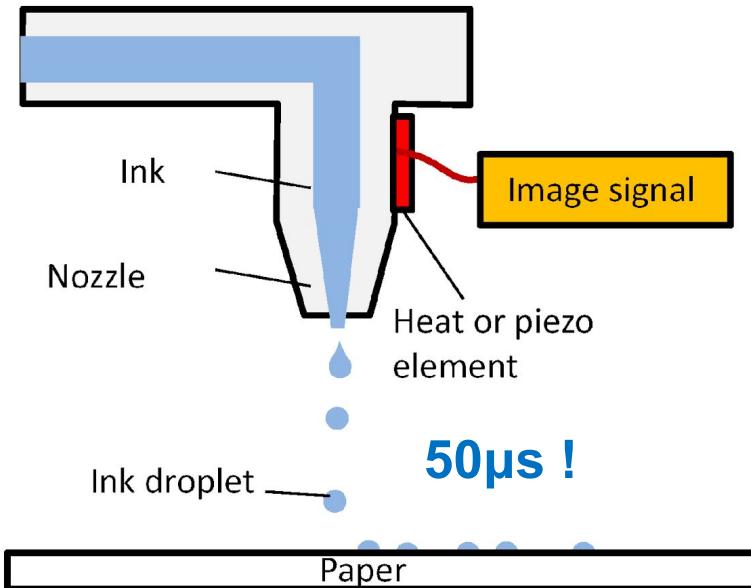




# 1 / Industrial & automotive

## • Nozzles

- Hewlett-Packard (HP)'s thermal inkjet technology (TIT)
- MicroParts' drug-inhaling device for asthma patients □ by LIGA process





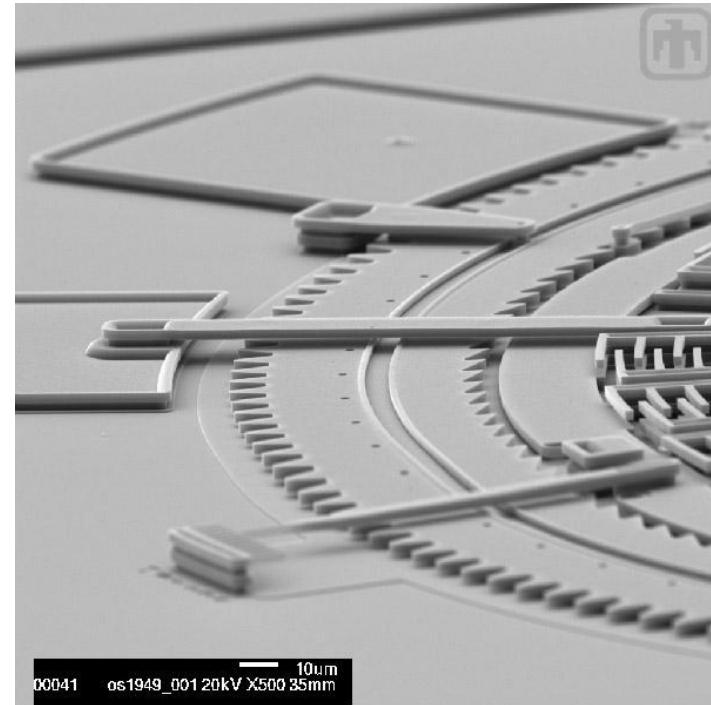
# 1 / Industrial & automotive

- Nuclear weapons

- Safety devices – stronglinks – have pattern gear discriminators that are fabricated by LIGA process



Detonator pellet

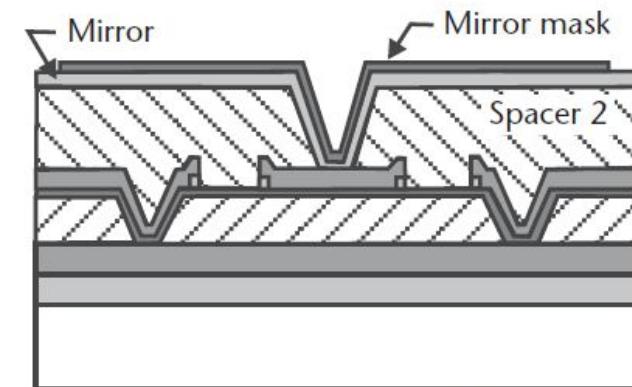
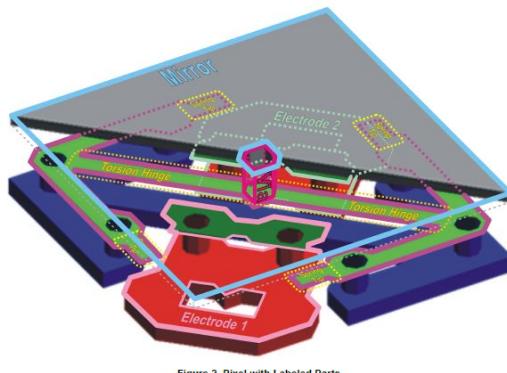
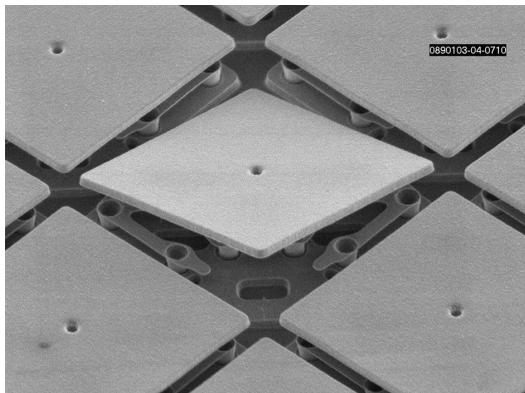


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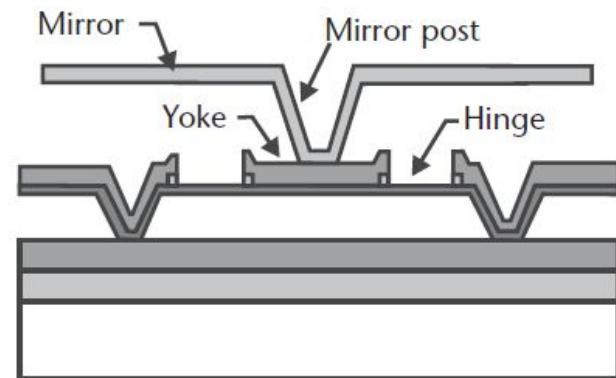


## 2 / Optical displays

- Texas Instruments' Digital Light Processing (DLP) Technology
  - Digital micromirror device (DMD)
  - Spatial light modulator/switch



5. Deposit spacer 2 and mirror



6. Pattern mirror and etch sacrificial spacers



## 2 / Optical displays

- Video – how does it work?
- <http://www.ti.com/general/docs/video/watch.tsp?entryid=5157963226001>

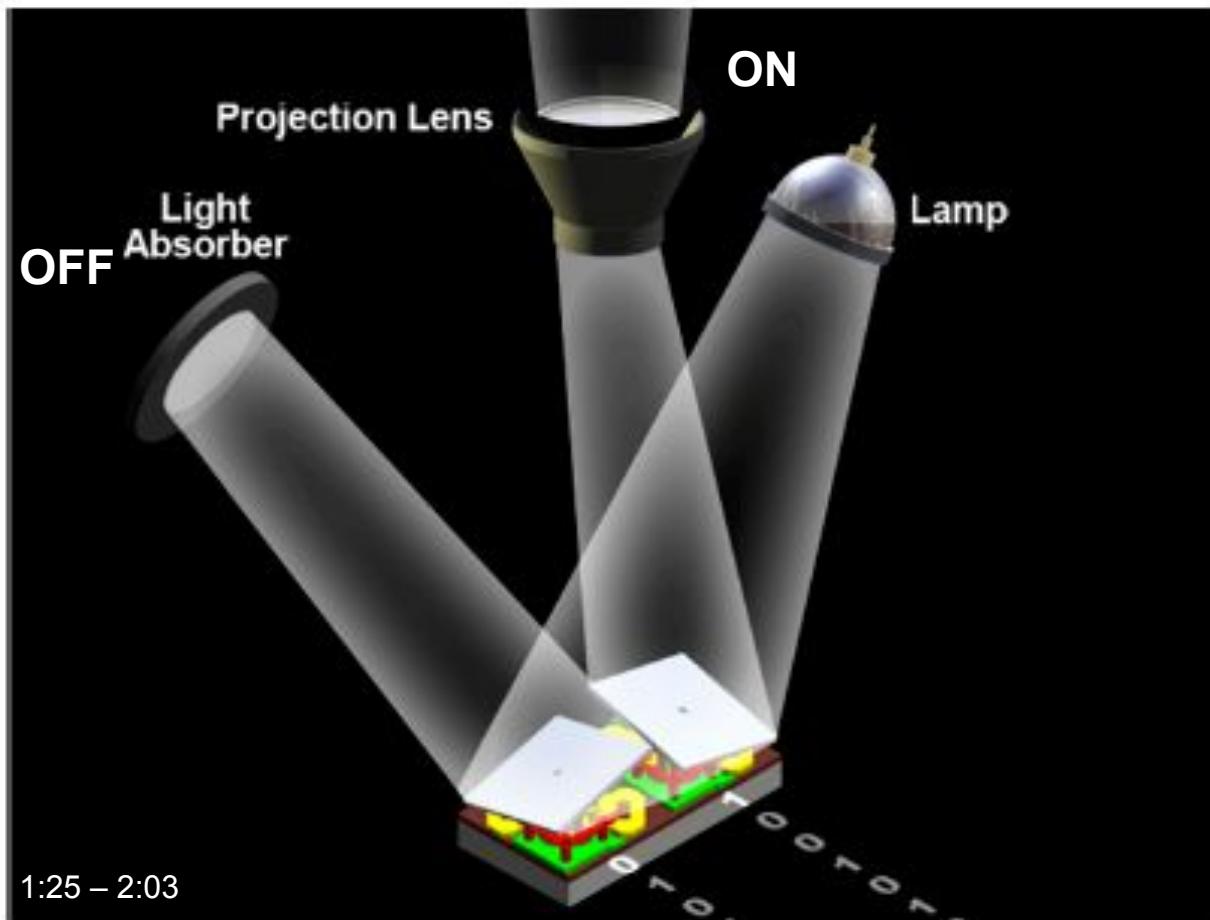


Figure 1. Pixels in On and Off State



## 2 / Optical displays

- Reliability
  - Hinge fatigue
  - Shock & vibration failure



# Outlook for MEMS

## Strength

- Provides a customized technical solution for a particular application
- Many tools to choose from

## Limitation

- Doesn't have any standards
- Not many high-volume manufacturing applications
  - Absence of “the killer app”
- Diverging demands & fragmentation
- Poor forecasting & investments

## To MEMS or not to MEMS?

- Enabling a new function, cost reduction, reliability



*Thank  
You*

MEMS

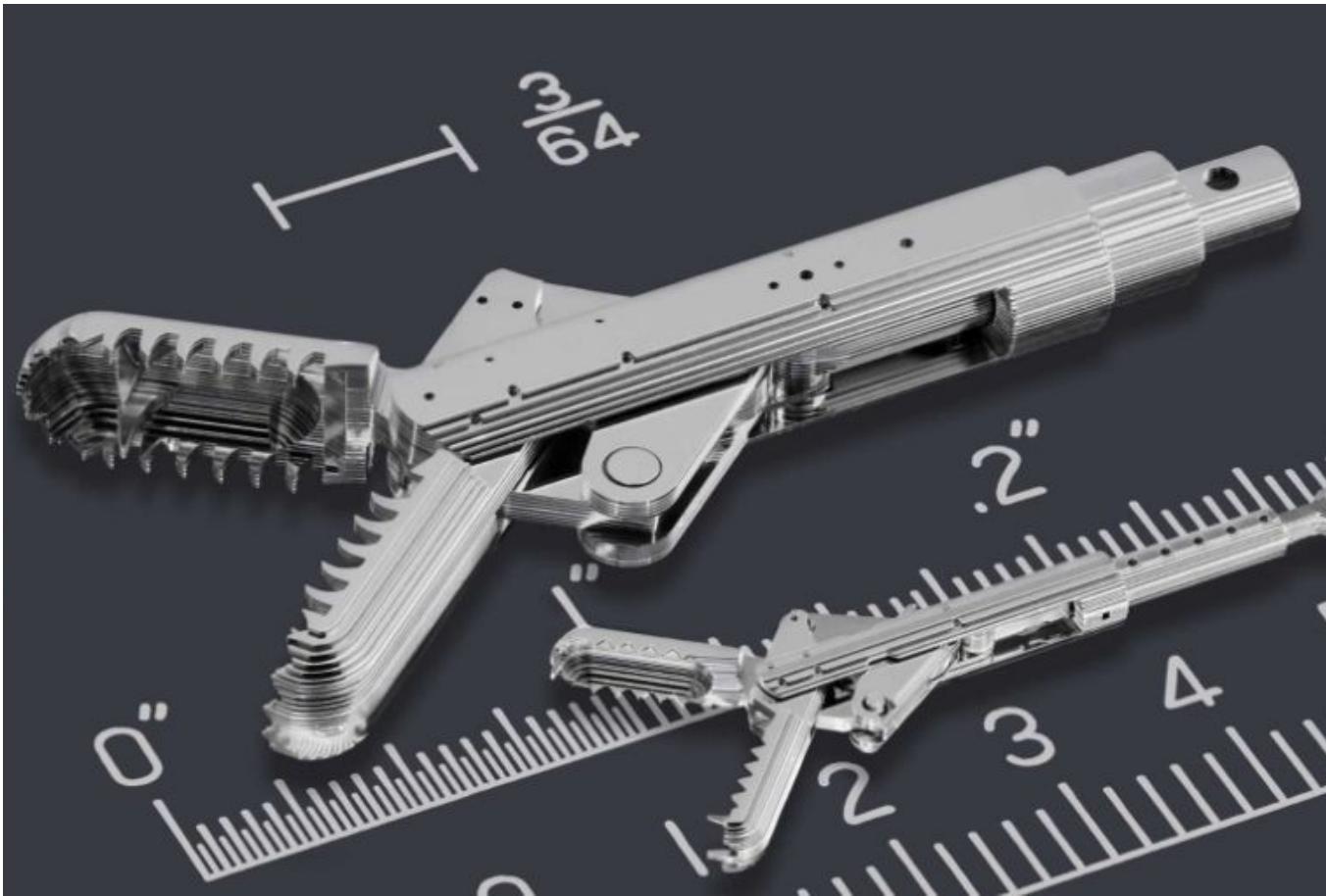


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# MEMS is evolving ...

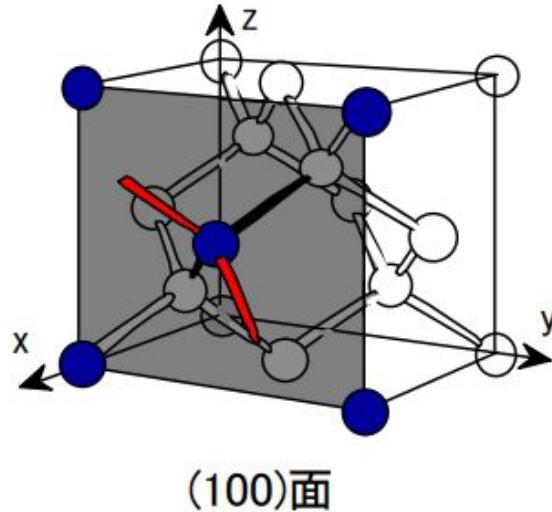


*Microfabrica*

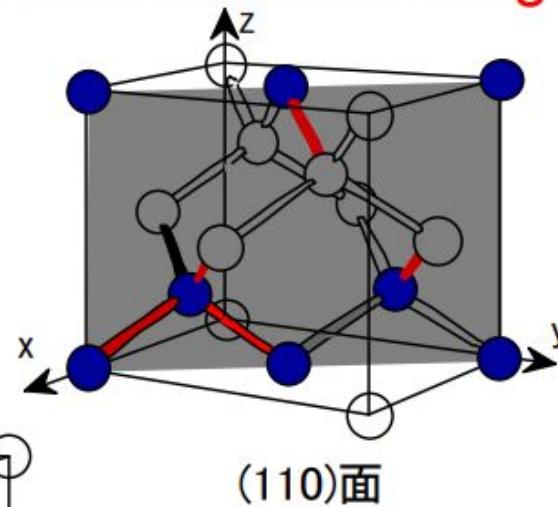


# Miller indices of Silicon

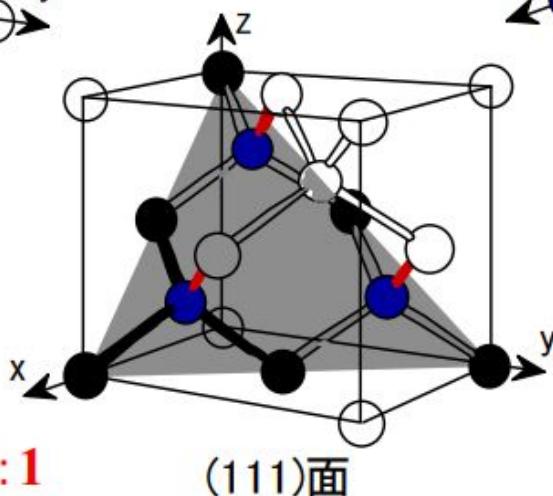
Hypothesis: Number of dangling bond appearing on the silicon surface determines the etching rate



Dangling bond: 2  
Back bond: 2



Dangling bond: 1 + (2)  
(Exposed back bond: 2)  
Back bond: 3



Dangling bond: 1  
Back bond: 3